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APPLICATION NO.	1	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
, 10/721,874	10/721,874 11/26/2003		Takashi Kobayashi	XA-10000	6095	
181	7590	01/12/2006		EXAM	EXAMINER	
		BRIDGE PC	ERDEM,	ERDEM, FAZLI		
1751 PINNA SUITE 500	ACLE DR	RIVE	ART UNIT	PAPER NUMBER		
MCLEAN,	VA 221	02-3833	2826			
				DATE MAILED: 01/12/2006	4	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)	Applicant(s)				
		10/721,874	KOBAYASHI ET AL.					
	Office Action Summary	Examiner	Art Unit	- (M)				
		Fazli Erdem	2826					
Period fo	The MAILING DATE of this communication ap or Reply	pears on the cover sheet w	ith the correspondence ad	dress				
WHIC - Exte after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLICHEVER IS LONGER, FROM THE MAILING Designs of time may be available under the provisions of 37 CFR 1. SIX (6) MONTHS from the mailing date of this communication. Operiod for reply is specified above, the maximum statutory period for reply within the set or extended period for reply will, by statute the provision of the control of the control of the mailing education of the control of the mailing education of the control of the contro	DATE OF THIS COMMUN 136(a). In no event, however, may a will apply and will expire SIX (6) MO le, cause the application to become A	CATION. reply be timely filed NTHS from the mailing date of this co BANDONED (35 U.S.C. § 133).					
Status								
1)🖂	Responsive to communication(s) filed on 31 (October 2005.						
• • • • •		s action is non-final.						
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.							
Disposit	ion of Claims							
4) 🖾	Claim(s) <u>1,2,4-21 and 23-29</u> is/are pending in the application.							
	4a) Of the above claim(s) is/are withdrawn from consideration.							
5)	Claim(s) is/are allowed.							
6)🛛	Claim(s) <u>1,2,4,9-11,13,18,20,21,23,28 and 29</u> is/are rejected.							
7)🛛	Claim(s) <u>5-8,12,14-17,19 and 24-27</u> is/are objected to.							
8)	Claim(s) are subject to restriction and/o	or election requirement.						
Applicati	ion Papers							
9) ☐ The specification is objected to by the Examiner.								
10)	10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.							
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).							
11)	11)☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority (under 35 U.S.C. § 119							
	Acknowledgment is made of a claim for foreigi ☐ All b)☐ Some * c)☐ None of: 1.☐ Certified copies of the priority documen		§ 119(a)-(d) or (f).					
	2. Certified copies of the priority documen		Application No.					
	3. Copies of the certified copies of the prior		- · ·	Stage				
	application from the International Burea	, ,,,						
* See the attached detailed Office action for a list of the certified copies not received.								
A44	W-1							
Attachmen	t(s) e of References Cited (PTO-892)	A) Interview	Summary (PTO-413)					
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date								
	nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date) 5)	Informal Patent Application (PTO)-152)				
Patent and T			·					

DETAILED ACTION

Election restriction that was issued by examiner on August 26, 2004 has been vacated.

Allowable Subject Matter

1. Claims 5-8, 12, 14-17, 19 and 24-27 objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 1, 2, 4, 9-11, 13, 18, 20, 21, 23, 28 and 29 rejected under 35 U.S.C. 103(a) as being unpatentable over Eitan (6,011,725) in view of Fan et al. (6,834,013) further in view of Taira et al. (6,410,412)

Regarding Claims 1, 2, 4, 9-11, 13, 18, 20, 21, 23, 28 and 29, Eitan discloses a two bit non-volatile electrically erasable and programmable semiconductor memory cell utilizing asymmetrical charge trapping where in Figs. 1-5, it is disclose a first insulator film 56 formed above a semiconductor substrate 62, silicon nitride dots charge trapping layer 54 formed on the first insulator layer 56, a second insulator film formed on silicon nitride dots charge trapping layer, a conductive film 50 formed above the second insulator film 52, a channel region formed in semiconductor substrate 62 and disposed between semiconductor source/drain regions 58 and 60. Eitan fails to disclose the

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required programming structure and the required heights of the insulating and the dot/particulate layers. However, Fan et al. disclose a method for programming and erasing non-volatile memory with nitride tunneling layer where in abstract section and in columns 1 and 3, programming is performed by injecting charges from channel region into silicon nitride charge trapping layer. Furthermore, Taira et al. disclose methods for fabricating memory devices where in Fig. 13, the insulating layers 6 and 11 have heights greater than the height of the dot/particulate layer 9.

Regarding Claim 2, Figs. 1-5 of Eitan disclose the required programming direction.

Regarding Claim 9, silicon nitride dots charge trapping layer 54 of Eitan is present as a single layer.

It would have been obvious to one of having ordinary skill in the art at the time the invention was made to include the required programming by injection of charges from channel region into silicon nitride charge trapping region and the required height of the insulating and the particle/dot layers, in order to have a nonvolatile semiconductor memory cell with increased performance and reliability.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fazli Erdem whose telephone number is (571) 272-1914. The examiner can normally be reached on M - F 8:00 - 5:00.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan Flynn can be reached on (571) 272-1915. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Paterio Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

FΕ January 6, 2006